

L Number	Hits	Search Text	DB	Time stamp
4	21	((polishing near solution) slurry) SAME (monitor monitors monitoring sense sensor sensors sensing) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/24 14:43
5	26	(monitor monitors monitoring sense sensor sensors sensing) with turbidity same electromagnetic	USPAT; US-PGPUB; EPO; JPO	2003/10/24 13:36
28	15	("4070797" "4156619" "4563257" "4724042" "5193316" "5320706" "5489233" "5584146" "5616212" "5704987" "5738800" "5759917" "5930645" "6046112" "6120571").PN.	USPAT	2003/10/24 14:40
29	21	((polishing near (fluid solution)) slurry) SAME (monitor monitors monitoring sense sensor sensors sensing) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/24 14:49
32	1	((polishing near (fluid solution)) slurry) with electromagnetic with (monitor monitors monitoring sense sensor sensors sensing) same turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/24 15:17
33	1	((polishing near (fluid solution)) slurry) with electromagnetic with (monitor monitors monitoring sense sensor sensors sensing) and turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/24 14:50
34	2	(fluid solution slurry) with electromagnetic with (monitor monitors monitoring sense sensor sensors sensing) SAME turbidity and (polishing planarization)	USPAT; US-PGPUB; EPO; JPO	2003/10/24 14:56
35	2	("5291626" "5446531").PN.	USPAT	2003/10/24 14:54
36	2	(fluid solution slurry) with electromagnetic with (monitor monitors monitoring sense sensor sensors sensing) SAME turbidity and (insulate insulates insulated insulating)	USPAT; US-PGPUB; EPO; JPO	2003/10/24 14:57
37	0	(fluid solution slurry) with electromagnetic with (monitor monitors monitoring sense sensor sensors sensing) SAME turbidity and (split splitting)	USPAT; US-PGPUB; EPO; JPO	2003/10/24 14:57
38	3	(fluid solution slurry) with electromagnetic with (monitor monitors monitoring sense sensor sensors sensing) and turbidity and (split splitting)	USPAT; US-PGPUB; EPO; JPO	2003/10/24 14:57
43	580	451/\$.ccls. and (semiconductor wafer substrate) and (slurry solution) and (supply supplies supplying) and (sensor monitor)	USPAT; US-PGPUB; EPO; JPO	2003/10/24 15:08
44	7	(451/\$.ccls. and (semiconductor wafer substrate) and (slurry solution) and (supply supplies supplying) and (sensor monitor)) and turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/24 15:08
55	86	(sensor sensors) with (monitor monitors monitoring) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/24 15:18
-	2496	451/41.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 16:06
-	8	slurry with (monitor monitoring) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/15 14:45
-	281525	electromagnetic slurry with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/15 14:36
-	1	electromagnetic with slurry with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/15 14:38
-	1	6409936.pn.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 14:38
-	8	slurry same (monitor monitoring) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/15 14:44
-	3	(polishing near solution) with (monitor monitoring) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/24 13:34
-	3	(polishing near solution) SAME (monitor monitoring) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/22 12:50

-	0	09324737.ap.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 14:48
-	5	324737.ap.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 14:48
-	1330	451/5.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 16:06
-	644	451/6.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 16:06
-	711	451/8.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 16:06
-	1305	451/28.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 16:07
-	796	451/36.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 16:07
-	410	451/60.ccls.	USPAT; US-PGPUB; EPO; JPO	2003/10/15 16:08
-	4	(451/41.ccls. 451/5.ccls. 451/6.ccls. 451/8.ccls. 451/28.ccls. 451/36.ccls. 451/60.ccls.) and turbidity with (monitor monitoring)	USPAT; US-PGPUB; EPO; JPO	2003/10/15 16:09
-	14	((polishing near solution) slurry) WITH (monitor monitors monitoring sense sensor sensors sensing) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/22 12:56
-	20	((polishing near solution) slurry) SAME (monitor monitors monitoring sense sensor sensors sensing) with turbidity	USPAT; US-PGPUB; EPO; JPO	2003/10/24 13:34